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INTERVIEW

Wen-li Wu talks about advances in x-ray-based semiconductor metrology

Qinghuang Lin*
JM3 Associate Editor

ABSTRACT. JM3 Associate Editor Qinghuang Lin interviews Wen-li Wu, retired from the National Institute of Standards and Technology. With R. Joseph Kline, Ronald L. Jones, Hae-Jeong Lee, Eric K. Lin, Daniel F. Sunday, Chengqing Wang, Tengjiao Hu, and Christopher L. Soles, Wu is the lead author of "Review of the key milestones in the development of critical dimension small angle x-ray scattering at National Institute of Standards and Technology," a review paper in the Special Section on 3D Metrology in the July–September 2023 issue of the *Journal of Micro/Nanopatterning, Materials, and Metrology*.

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Dr. Wen-li Wu, retired from the National Institute of Standards and Technology, authored a JM3 review paper on advances in x-ray-based semiconductor metrology. Watch the interview at https://doi.org/10.1117/1.JMM.22.3.030701.s1

*Address all correspondence to Qinghuang Lin, qinghuang.lin@gmail.com

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